POSTERS NANOSCALE 2023

The area for the posters is **97 cm (wide) x 118 cm (high)**, i. e. A0 format fits well.

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P-12 p. 119	**Generation and measurement of sub nanoradian angles** 1) Andrew Yacoot* 2) Simon Alcock, Rabia Ince and Hiten Patel 1) National Physical Laboratory, Teddington, United Kingdom 2) Diamond Light Source, Didcot, Oxfordshire, United Kingdom
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P-14 p. 127	**Compensation method of measurement deviation by the lateral positioning axis for topography measurements with heterodyne Interferometry** 1) Dennis Leitz*, Christian Rembe 2) Sai Gao 1) Institute of Electrical Information Technology, TU Clausthal, Germany 2) Physikalisch-Technische Bundesanstalt (PTB), Braunschweig, Germany
P-15 p. 133	**Periodic nonlinearities of the fiber interferometric sensor in comparison to commercial homodyne interferometer** V. Shmagun*, T. Kissinger, T. Fröhlich Technical University of Ilmenau, Ilmenau, Germany

P-16 p. 137	**Modified common-path differential interferometer with balanced arms and sub-nanometre long-term zero drifts** M. Hola*, S. Rerucha*, J. Lazar, O. Cip Institute of Scientific Instruments of the CAS (ISI), Brno, Czechia
P-17 p. 139	**Characterising and tackling thermally induced zero-drift in displacement measuring interferometry** S. Rerucha*, M. Hola, J. Lazar, O. Cip Institute of Scientific Instruments of the CAS (ISI), Brno, Czechia
P-18 p. 143	**Gauge block interferometer designed for gauge blocks calibration with modified uncertainty budget** 1) Yasser A. AlTalhh, Abdulhakim N. AlZamil, Nasser M. AlQahtani 2) Khaled M. Ahmed* 1) SASO-NMCC (Saudi Arabia) 2) SASO-NMCC (Saudi Arabia) and NIS (Egypt)

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